

## Temperature dependence of tunnel magnetoresistance of IrMn based MTJ

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The temperature dependence of spin-polarized tunneling magnetoresistance ( $TMR=(R_A-R_P)/R_A$ ) is investigated between 30 K and 300 K for as deposited and annealed junctions with the structure of Ta(5)/Cu(10)/Ta(5)/NiFe(2)/Cu(5)/IrMn(10)/CoFe(2.5)/Al-O/CoFe(2.5)/NiFe(t)/Ta(5), where  $t = 10$  and 100 nm. MTJ's were prepared on thermally oxidized Si wafers using DC magnetron sputtering with ultra clean Ar(9N) as the process gas, in a chamber with base pressure of  $4 \times 10^{-9}$  hPa [1]. The samples were annealed in vacuum ( $10^{-6}$  hPa) at 200°C, 270°C and 300°C for 1 hour under a magnetic field of 80 kA/m, followed by field cooling. The junction magnetoresistance decreased for annealed samples at 270°C and 300°C (where maximum of TMR is observed) and increased for as deposited and annealed at 200°C with increasing temperature (Fig.1). The experimental results of TMR of the junction with  $t = 100$  nm are successfully described by a model that includes electron polarization  $P$  that decreases with  $T$  due to thermally excited spin waves according to  $P \propto (1 - \alpha T^{3/2})$  [2], Fig.2. From Julliere's model it can be obtained that difference of parallel and antiparallel conductance is proportional to the electron spin polarizations of ferromagnetic electrodes  $\Delta G = G_P - G_A \propto P_1 P_2$ .

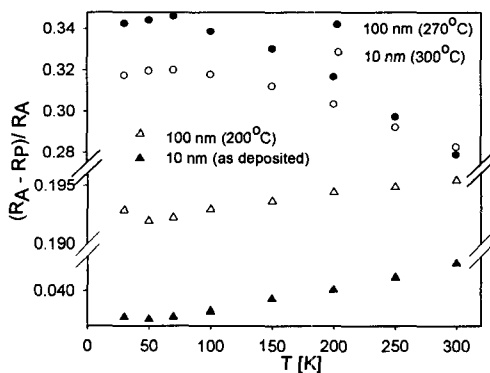


Fig.1

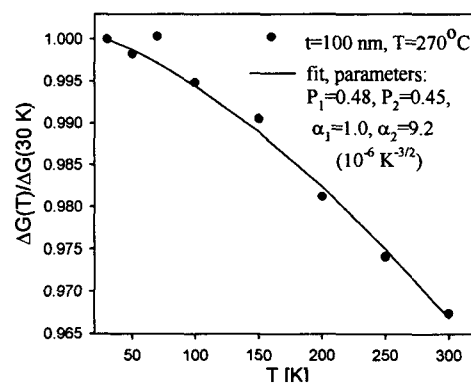


Fig.2

### References

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